

	Hit s	Search Text	DBs
27	1	(immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and (((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and (expos\$6 or illuminat\$4 or irradiat\$4) and (CAR or (chemical\$3 near8 amplif\$5 near6 resist) or ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5))) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3) same protective)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	5	(immersion near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and (((multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and (expos\$6 or illuminat\$4 or irradiat\$4) and (CAR or (chemical\$3 near8 amplif\$5 near6 resist) or ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5))) and (protective near9 layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
29	30	((immersion or liquid) near14 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and ((multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and (expos\$6 or illuminat\$4 or irradiat\$4) and (CAR or (chemical\$3 near8 amplif\$5 near6 resist) or ((acid or photo\$4acid or (therm\$5 near6 acid)) near15 (generat\$4 or liberat\$5))) and (protective near9 layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	3	(immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) and (resist or photoresist or photosensitive or photo\$5cur\$5 or (radiation near9 sensitive)) and (((double near9 \$5resist) or (dual\$5 near5 resist\$5 near5 layer) or multilayer or bilayer or bi\$4layer or tri\$2layer) same (resist or photoresist or imag\$3)) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3) same protective)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
31	6	(immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4)) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3) same (protective near12 layer) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
32	10	((immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4) or IML) and ((prevent\$5 or avoid\$4) same (infus\$4 or penetrat\$4 or diffus\$3 or interact\$5) same ((protective near12 layer) or topcoat) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5))	US-PPGUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
33	5	((immersion near22 (lithograph\$8 or photolitho\$8 or expos\$4) or IML) and ((protective near12 layer) or topcoat) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) same ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4))))	US-PPGUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
34	23	((protective near12 layer) or topcoat) same (photoresist or resist or photosensitive or imag\$3 or photoimag\$5) same ((chemical\$5 near9 amplif\$4 near5 resist) or PAG or (photoacid near5 generat\$4) or (acid near6 (diffus\$4 or generat\$4))) same (diffusion or penetrat\$\$ or infus\$4))	US-PPGUB; USPAT; EPO; JPO; DERWENT; IBM_TDB